



The Fine Line : Videos for the eBeam Community Spring 2015

Shot Talk - A Word from Our Sponsor

Aki Fujimura, CEO of D2S, recaps highlights from the SPIE Advanced Lithography Conference including takeaways from the 7th annual eBeam Initiative SPIE luncheon, and extends an invitation to attend the eBeam Initiative workshop at the upcoming Photomask Japan symposium.



Tech Talk

Takayuki Nakamura of Advantest brings mask defects at the 1X node into focus with an overview of new 2D- and 3D-based mask defect verification methodologies utilizing simulation technology from D2S. Such methodologies can reduce the AIMS work load and, therefore, the turnaround time of mask manufacturing.



Perspectives

Colin Harris, founder and COO of PMC-Sierra, provides a fabless chipmaker's perspective on the impact of complex mask shapes, discusses the impact of big data on his company's business and challenges the industry to extend Moore's Law beyond the 16nm node.



Video Archive

The Fine Line Autumn Edition



Shot Talk: Aki Fujimura of D2S



From the White Board:
Kang-Hoon Choi, Fraunhofer
CNT



Tech Talk: [Aki Fujimura](#) teams
up with [Bob Pack](#) of
GLOBALFOUNDRIES



Perspectives:
Industry luminary panel at
BACUS 2014 with IBM,
GLOBALFOUNDRIES, NuFlare
and D2S

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The eBeam Initiative provides a forum for educational and promotional activities regarding new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please e-mail requests@ebeaminitiative.org or visit www.ebeaminitiative.org